

	Hits	Search Text	DBs
38	13	((immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) or IML or (liquid near12 lithography)) and (((protective near12 layer) or topcoat or (ARC near26 diffus\$4)) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) same ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
39	36	(((protective near12 layer) or topcoat or (ARC near26 diffus\$4) or (protective near26 diffus\$4)) near22 (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) near39 ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4))) same (heat\$4 or bak\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
40	59	(((protective near12 layer) or topcoat or (ARC near26 diffus\$4) or (protective near26 diffus\$4)) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) same ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4))) same (heat\$4 or post\$4bak\$4 or post\$4heat\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB